

## *1st Announcement and Call for Papers*

18-20 April 2018

Pacifico Yokohama

Yokohama, Japan

# Photomask Japan 2018

*The 25th Symposium on  
Photomask and NGL Mask Technology*

*Symposium Chair:*

**Masato Shibuya**

**Tokyo Polytechnic University**

**Abstract Due Date:  
November 30, 2017**

**Camera-Ready Abstract  
Due Date:  
February 1, 2018**

**Manuscript Due Date:  
March 14, 2018**

**P**hotomask Japan 2018 is the 25th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and investigators from Japan, USA, and all over the world in the field of photomasks, NGL masks, and related technologies to discuss recent progress, applications, and future trends. The conference program will feature invited papers, contributed papers, poster sessions, and a rump session with panel discussion. Display opportunities will be provided to mask manufacturing materials, and equipment companies.

*Papers are solicited on the following and related topics:*

- **Materials for Photomasks**
- **Fabrication Process Steps and Equipments for Photomasks (process and equipments for developing, etching, cleaning etc.)**
- **Photomask Writing Tools and Technologies including multi-EB writers**
- **Tools and Technologies for Metrology/ Inspection/Repair**
- **Technologies and infrastructures for EUVL/NIL/FPD masks**
- **Mask Data Preparations, EDA and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and Multiple Patterning**
- **Photomask-relating Lithography Technologies**
- **DSA (Directed Self-Assembly) related mask technologies**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**
- **Mask/Lithography related Technology in Academia (Poster Session)**

Concrete information will be announced at the 2<sup>nd</sup> Call for Papers.

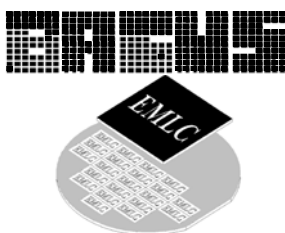
Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English

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For more information, contact:  
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### *Abstract Submissions*

All authors are *strongly encouraged* to submit their abstract by the due date, November 30 2017 via the PMJ official website. Abstract submission Web page will be opened from October 2017 at:

**<http://www.photomask-japan.org/>**

Further information and instruction will be available from 2nd Announcement & Call for Papers, which will be published around September, 2017

**\*Please do not send the abstract by e-mail or FAX.**

### *Conference Site*

Conference site of Photomask Japan 2018 will be "Annex Hall" at Pacifico Yokohama